## **ACKNOWLEDGEMENT RECEIPT**

Electronic Version 1.1

Stylesheet Version v1.1.1

Title of Invention

## HIGH-PRESSURE PROCESSING CHAMBER FOR A SEMICONDUCTOR WAFER

Submision Type: Information Disclosure

Statement

Application Number:

Server Response:

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File Listing:

Doc. Name	File Name	Size (Bytes)	Date
			Produced
			(yyyymmdd)
us-ids	SSI04001-usidst.xml	1762	2005-05-16
us-ids	us-ids.dtd	7763	2005-05-16
us-ids	us-ids.xsl	12026	2005-05-16
package-data	SSI04001-pkda.xml	1706	2005-05-16
package-data	package-data.dtd	27025	2005-05-16
package-data	us-package-data.xsl	19263	2005-05-16
	Total files size	69545	

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